L Number	Hits	Search Text	DB	Time stamp
-	19	(SiON or "silicon oxynitride") and ("tetramethyl ammonium	USPAT;	2003/04/24
ì		hydroxide" or TMAH) and ("isopropyl alcohol" or IPA)	US-PGPUB	12:02
- '	16	((SiON or "silicon oxynitride") and ("tetramethyl ammonium	USPAT;	2003/04/15 11:42
		hydroxide" or TMAH) and ("isopropyl alcohol" or IPA)) not	US-PGPUB	
		(@ad>20020109 or @rlad>20020109)		
-	5	(((SiON or "silicon oxynitride") and ("tetramethyl ammonium	USPAT;	2003/04/09
		hydroxide" or TMAH) and ("isopropyl alcohol" or IPA)) not	US-PGPUB	15:50
-		(@ad>20020109 or @rlad>20020109)) and 438/\$.ccls.		
-	182	(SiON or "silicon oxynitride") and ("tetramethyl ammonium	USPAT;	2003/04/24
		hydroxide" or TMAH)	US-PGPUB	12:02
-	507	(SiON or "silicon oxynitride") and ("isopropyl alcohol" or IPA)	USPAT;	2003/04/09
1			US-PGPUB	15:50
-	О	438/692.ccls. and ((SiON or "silicon oxynitride") and	USPAT;	2003/04/09
		("tetramethyl ammonium hydroxide" or TMAH))	US-PGPUB	15:50
-	1	438/692.ccls. AND ((SiON or "silicon oxynitride") and	USPAT;	2003/04/09
}		("isopropyl alcohol" or IPA))	US-PGPUB	15:52
-	89	438/749.ccls.	USPAT;	2003/04/09
- 1			US-PGPUB	15:53
-	1	((SiON or "silicon oxynitride") and ("tetramethyl ammonium	USPAT;	2003/04/09
		hydroxide" or TMAH)) and 438/749.ccls.	US-PGPUB	15:54
-	0	((SiON or "silicon oxynitride") and ("isopropyl alcohol" or	USPAT;	2003/04/09
		IPA)) and 438/749.ccls.	US-PGPUB	15:54
-	160	438/750.ccls.	USPAT;	2003/04/09
			US-PGPUB	15:55
-	0	((SiON or "silicon oxynitride") and ("tetramethyl ammonium	USPAT;	2003/04/09
		hydroxide" or TMAH)) and 438/750.ccls.	US-PGPUB	15:55
-	О	((SiON or "silicon oxynitride") and ("isopropyl alcohol" or	USPAT;	2003/04/09
		IPA)) and 438/750.ccls.	US-PGPUB	15:55
-	110	438/751.ccls.	USPAT;	2003/04/09
			US-PGPUB	15:55
-	0	((SiON or "silicon oxynitride") and ("isopropyl alcohol" or	USPAT;	2003/04/09
		IPA)) and 438/751.ccls.	US-PGPUB	15:55
-	1	((SiON or "silicon oxynitride") and ("tetramethyl ammonium	USPAT;	2003/04/09
		hydroxide" or TMAH)) and 438/751.ccls.	US-PGPUB	15:56
-	361	438/906.ccls.	USPAT;	2003/04/09
			US-PGPUB	15:56
-	0	((SiON or "silicon oxynitride") and ("tetramethyl ammonium	USPAT;	2003/04/09
		hydroxide" or TMAH)) and 438/906.ccls.	US-PGPUB	15:56
-	2	((SiON or "silicon oxynitride") and ("isopropyl alcohol" or	USPAT;	2003/04/09
		IPA)) and 438/906.ccls.	US-PGPUB	16:03
-	293	438/974.ccls.	USPAT;	2003/04/09
			US-PGPUB	16:03
-	0	((SiON or "silicon oxynitride") and ("tetramethyl ammonium	USPAT;	2003/04/09
		hydroxide" or TMAH)) and 438/974.ccls.	US-PGPUB	16:03
-	0	((SiON or "silicon oxynitride") and ("isopropyl alcohol" or	USPAT;	2003/04/09
ļ	_	(PA)) and 438/974.ccls.	US-PGPUB	16:03
-	821	(SiON or "silicon oxynitride") and hydrophobic	USPAT;	2003/04/09
		0/1 1 1//01037 # 71	US-PGPUB	16:04
-	86	438/\$.ccls. and ((SiON or "silicon oxynitride") and	USPAT;	2003/04/09
		hydrophobic)	US-PGPUB	16:04
-	72	(438/\$.ccls. and ((SiON or "silicon oxynitride") and	USPAT;	2003/04/09
1		hydrophobic)) not (@ad>20020109 or @rlad>20020109)	US-PGPUB	16:04
-	43622	platen	USPAT;	2003/04/09
			US-PGPUB	16:04
-	1	((438/\$.ccls. and ((SiON or "silicon oxynitride") and	USPAT;	2003/04/09
l		hydrophobic)) not (@ad>20020109 or @rlad>20020109))	US-PGPUB	16:05
		and platen		
- '	5	(SiON or "silicon oxynitride") and ("tetramethyl ammonium	USPAT;	2003/04/09
1		hydroxide" or TMAH) and platen	US-PGPUB	16:07
-	5	((SiON or "silicon oxynitride") and ("tetramethyl ammonium	USPAT;	2003/04/09
		hydroxide" or TMAH) and platen) not (@ad>20020109 or	US-PGPUB	16:05
1		@rlad>20020109)		
-	10	(SiON or "silicon oxynitride") and ("isopropyl alcohol" or IPA)	USPAT;	2003/04/09
		and platen	US-PGPUB	16:07

•	9	((SiON or "silicon oxynitride") and ("isopropyl alcohol" or IPA) and platen) not (@ad>20020109 or @rlad>20020109)	USPAT; US-PGPUB	2003/04/09 17:01
-	24	438/for.111.ccls.	EPO; JPO;	2003/04/10
-	571	remov\$3 with (SiON or "silicon oxynitride")	DERWENT USPAT;	09:54 2003/04/10
-	19	(remov\$3 with (SiON or "silicon oxynitride")) and	US-PGPUB USPAT;	10:42 2003/04/10
	15	("tetramethyl ammonium hydroxide" or TMAH) ((remov\$3 with (SiON or "silicon oxynitride")) and	US-PGPUB	10:43
	17	("tetramethyl ammonium hydroxide" or TMAH)) not (@ad>20020109 or @rlad>20020109)	USPAT; US-PGPUB	2003/04/15 11:57
-	4	(remov\$3 with (SiON or "silicon oxynitride")) and ("isopropyl alcohol" or IPA)	USPAT; US-PGPUB	2003/04/10 10:46
-	4	((remov\$3 with (SiON or "silicon oxynitride")) and ("isopropyl alcohol" or IPA)) not (@ad>20020109 or @rlad>20020109)	USPAT; US-PGPUB	2003/04/15 11:57
-	14469	(polish\$3 or CMP) with (partial or partially or thickness)	USPAT; US-PGPUB	2003/04/15 11:59
-	391	438/626.ccls.	USPAT; US-PGPUB	2003/04/15 11:37
-	73	((polish\$3 or CMP) with (partial or partially or thickness)) and 438/626.ccls.	USPAT; US-PGPUB	2003/04/15 11:38
-	20	(SiON or "silicon oxynitride") and (((polish\$3 or CMP) with (partial or partially or thickness)) and 438/626.ccls.)	USPAT; US-PGPUB	2003/04/15
-	О	((SiON or "silicon oxynitride") with ("tetramethyl ammonium	USPAT;	2003/04/15
		hydroxide" or TMAH) and ("isopropyl alcohol" or IPA)) not (@ad>20020109)	US-PGPUB	12:00
-	0	((SiON or "silicon oxynitride") same ("tetramethyl ammonium hydroxide" or TMAH) and ("isopropyl alcohol" or IPA)) not	USPAT; US-PGPUB	2003/04/15 11:43
-	16	(@ad>20020109 or @rlad>20020109) ((SiON or "silicon oxynitride") and ("tetramethyl ammonium	USPAT;	2003/04/15 11:49
		hydroxide" or TMAH) and ("isopropyl alcohol" or IPA)) not (@ad>20020109 or @rlad>20020109)	US-PGPUB	
-	О	((polish\$3 or CMP) with (partial or partially or thickness)) and (((SiON or "silicon oxynitride") and ("tetramethyl ammonium	USPAT; US-PGPUB	2003/04/15 11:43
		hydroxide" or TMAH) and ("isopropyl alcohol" or IPA)) not (@ad>20020109 or @rlad>20020109))	OS-LGLOD	
-	44880	((SiON or "silicon oxynitride") and ("tetramethyl ammonium	USPAT;	2003/04/15 11:44
		hydroxide" or TMAH) or ("isopropyl alcohol" or IPA)) not (@ad>20020109 or @rlad>20020109)	US-PGPUB	
-	375	((polish\$3 or CMP) with (partial or partially or thickness)) and (((SiON or "silicon oxynitride") and ("tetramethyl ammonium	USPAT; US-PGPUB	2003/04/15 11:44
		hydroxide" or TMAH) or ("isopropyl alcohol" or IPA)) not (@ad>20020109 or @rlad>20020109))		
-	23	(SiON or "silicon oxynitride") and (((polish\$3 or CMP) with (partial or partially or thickness)) and (((SiON or "silicon	USPAT; US-PGPUB	2003/04/15 11:47
		oxynitride") and ("tetramethyl ammonium hydroxide" or	00 1 GI OD	
		TMAH) or ("isopropyl alcohol" or IPA)) not (@ad>20020109 or @rlad>20020109)))		
-	582	438/633.ccls.	USPAT; US-PGPUB	2003/04/15 11:47
-	47	((polish\$3 or CMP) with (partial or partially or thickness)) and (SiON or "silicon oxynitride") and 438/633.ccls.	USPAT; US-PGPUB	2003/04/15 11:47
-	50081	("tetramethyl ammonium hydroxide" or TMAH) or ("isopropyl alcohol" or IPA)	USPAT; US-PGPUB	2003/04/15
-	1	(((polish\$3 or CMP) with (partial or partially or thickness)) and (SiON or "silicon oxynitride") and 438/633.ccls.) and (	USPAT;	2003/04/15 11:51
		("tetramethyl ammonium hydroxide" or TMAH) or ("isopropyl	US-PGPUB	
-	1429	alcohol" or IPA)) 438/692.ccls.	USPAT; US-PGPUB	2003/04/15 11:51
-	1	(("tetramethyl ammonium hydroxide" or TMAH) or	USPAT;	2003/04/15 11:51
		("isopropyl alcohol" or IPA)) and (((polish\$3 or CMP) with (partial or partially or thickness)) and (SiON or "silicon	US-PGPUB	
-	41	oxynitride") and 438/692.ccls.) ((polish\$3 or CMP) with (partial or partially or thickness)) and	USPAT;	2003/04/15 11:55
		(SiON or "silicon oxynitride") and 438/692.ccls.	US-PGPUB	-5, - 1, -555

r					
	-	751	438/672.ccls.	USPAT; US-PGPUB	2003/04/15 11:55
	-	0	( ("tetramethyl ammonium hydroxide" or TMAH) or	USPAT;	2003/04/15 11:55
			("isopropyl alcohol" or IPA)) and (((polish\$3 or CMP) with	US-PGPUB	0, - 1, -005
İ		İ	(partial or partially or thickness)) and (SiON or "silicon		
1			oxynitride") and 438/672.ccls.)		
	-	17	((polish\$3 or CMP) with (partial or partially or thickness)) and (SiON or "silicon oxynitride") and 438/672.ccls.	USPAT;	2003/04/15 11:55
İ		0	((remov\$3 with (SiON or "silicon oxynitride"))with ("isopropyl	US-PGPUB USPAT;	222/21/22
			alcohol" or IPA)) not (@ad>20020109 or @rlad>20020109)	US-PGPUB	2003/04/15
	-	o	((remov\$3 with (SiON or "silicon oxynitride")) with	USPAT;	2003/04/15 11:59
			("tetramethyl ammonium hydroxide" or TMAH)) not	US-PGPUB	=000/04/101109
			(@ad>20020109 or @rlad>20020109)	İ	
1	•	1201	438/for.355.ccls.	EPO; JPO;	2003/04/15
				DERWENT;	11:58
	_	0	((remov\$3 with (SiON or "silicon oxynitride"))with ("isopropyl	IBM_TDB EPO; JPO;	0000/04/15 11/50
			alcohol" or IPA)) not (@ad>20020109 or @rlad>20020109)	DERWENT;	2003/04/15 11:59
			(20020109)	IBM_TDB	
	-	0	((remov\$3 with (SiON or "silicon oxynitride")) with	EPO; JPO;	2003/04/15 11:59
		0.01	("tetramethyl ammonium hydroxide" or TMAH)) not	DERWENT;	
			(@ad>20020109 or @rlad>20020109)	IBM_TDB	
	-	5910	(polish\$3 or CMP) with (partial or partially or thickness)	EPO; JPO;	2003/04/15 11:59
				DERWENT; IBM_TDB	
	-	2	438/for.355.ccls. and ((polish\$3 or CMP) with (partial or	EPO; JPO;	2003/04/15 11:59
			partially or thickness))	DERWENT;	2003/04/13 11:39
İ				IBM_TDB	
	-	6548	(SiON or "silicon oxynitride") with ("tetramethyl ammonium	EPO; JPO;	2003/04/15
			hydroxide" or TMAH)or ("isopropyl alcohol" or IPA)	DERWENT;	12:05
		О	408 /for acc cele and ((SiON on "ailion are mituide") with	IBM_TDB	
		U	438/for.355.ccls. and ((SiON or "silicon oxynitride") with ("tetramethyl ammonium hydroxide" or TMAH)or ("isopropyl	EPO; JPO; DERWENT;	2003/04/15
			alcohol" or IPA))	IBM_TDB	12:00
1	-	8	((polish\$3 or CMP) with (partial or partially or thickness)) and	EPO; JPO;	2003/04/15
			((SiON or "silicon oxynitride") with ("tetramethyl ammonium	DERWENT;	12:04
			hydroxide" or TMAH)or ("isopropyl alcohol" or IPA))	IBM_TDB	
	-	952640	semiconductor or "integrated circuit"	EPO; JPO;	2003/04/15
				DERWENT; IBM_TDB	12:04
	-	569	((SiON or "silicon oxynitride") with ("tetramethyl ammonium	EPO; JPO;	2003/04/15
		0-7	hydroxide" or TMAH)or ("isopropyl alcohol" or IPA)) and	DERWENT;	12:04
			(semiconductor or "integrated circuit")	IBM_TDB	•
-	-	3644	SiON or "silicon oxynitride"	EPO; JPO;	2003/04/15
				DERWENT;	12:05
	_	0	(((SiON or "silicon oxynitride") with ("tetramethyl ammonium	IBM_TDB	2002/24/25
		١	hydroxide" or TMAH)or ("isopropyl alcohol" or IPA)) and	EPO; JPO; DERWENT;	2003/04/15 12:05
			(semiconductor or "integrated circuit")) and (SiON or "silicon	IBM_TDB	12.05
			oxynitride")		
	-	13466	SiON or "silicon oxynitride"	USPAT;	2003/04/24
		4000		US-PGPUB	12:02
1	•	1824548	remov\$3 or etch\$3	USPAT;	2003/04/24
		1918183	remov\$3 or etch\$3 or clean\$3	US-PGPUB USPAT;	12:21
		1910103		US-PGPUB	2003/04/24 12:21
		1655	(SiON or "silicon oxynitride") with (remov\$3 or etch\$3 or	USPAT;	2003/04/24
			clean\$3)	US-PGPUB	12:13
1.		1474	((SiON or "silicon oxynitride") with (remov\$3 or etch\$3 or	USPAT;	2003/04/24
		64505	clean\$3)) not (@ad>20020109 or @rlad>20020109)	US-PGPUB	12:14
1	1	64587	438/\$.ccls.	USPAT;	2003/04/24
1.		1055	(((SiON or "silicon oxynitride") with (remov\$3 or etch\$3 or	US-PGPUB USPAT;	12:15 2003/04/24
		2000	clean\$3)) not (@ad>20020109 or @rlad>20020109)) and	US-PGPUB	12:18
L			438/\$.ccls.		

	·			
-	1436	438/692.ccls.	USPAT;	2003/04/24
		(((0)0))	US-PGPUB	12:16
-	32	((((SiON or "silicon oxynitride") with (remov\$3 or etch\$3 or	USPAT;	2003/04/24
		clean\$3)) not (@ad>20020109 or @rlad>20020109)) and	US-PGPUB	12:16
		438/\$.ccls.) and 438/692.ccls.		
-	4401	"tetramethyl ammonium hydroxide" or TMAH	USPAT;	2003/04/24
	46457	"icanganyl alashal" or IDA	US-PGPUB	12:17
-	46457	"isopropyl alcohol" or IPA	USPAT;	2003/04/24
_		(((SiON or "cilican argmitmide") with (name and a super-lands	US-PGPUB	12:17
-	0	(((SiON or "silicon oxynitride") with (remov\$3 or etch\$3 or clean\$3)) not (@ad>20020109 or @rlad>20020109)) with	USPAT;	2003/04/24
		("tetramethyl ammonium hydroxide" or TMAH)	US-PGPUB	12:18
l _	0	(((SiON or "silicon oxynitride") with (remov\$3 or etch\$3 or	TIODATE	
	0	clean\$3)) not (@ad>20020109 or @rlad>20020109)) with	USPAT;	2003/04/24
-		("isopropyl alcohol" or IPA)	US-PGPUB	12:18
1_	98856	hydrophobic	TIODAT.	0000/01/01
	90030	hydrophobic	USPAT; US-PGPUB	2003/04/24
_	3	(((SiON or "silicon oxynitride") with (remov\$3 or etch\$3 or	USPAT;	12:19
	3	clean\$3)) not (@ad>20020109 or @rlad>20020109)) with	US-PGPUB	2003/04/24 12:20
İ		hydrophobic	03-10101	12.20
_	1780212	remov\$3	USPAT;	2003/04/24
	1,00212	100.40	US-PGPUB	12:22
-	582	(SiON or "silicon oxynitride") with remov\$3	USPAT;	2003/04/24
	] 302	(Story or bineon oxymetrice) with removes	US-PGPUB	12:22
_	532	((SiON or "silicon oxynitride") with remov\$3 ) not	USPAT;	2003/04/24
	55-	(@ad>20020109 or @rlad>20020109)	US-PGPUB	12:22
<b>-</b>	13466	SiON or "silicon oxynitride"	USPAT;	2003/04/24
			US-PGPUB	12:24
-	1780212	remov\$3	USPAT;	2003/04/24
			US-PGPUB	12:24
-	944483	slurry or solution	USPAT;	2003/04/24
			US-PGPUB	12:25
-	964464	W or tungsten	USPAT;	2003/04/24
			US-PGPUB	14:07
-	46	(SiON or "silicon oxynitride") with remov\$3 with (slurry or	USPAT;	2003/04/24
		solution)	US-PGPUB	14:25
-	2	(W or tungsten) with ((SiON or "silicon oxynitride") with	USPAT;	2003/04/24
		remov\$3 with (slurry or solution))	US-PGPUB	14:07
-	123	conductive and dielectric and "silicon oxynitride" and	USPAT;	2003/04/24
		"titanium nitride" and (via or hole or opening or trench) and	US-PGPUB	14:27
		tungsten and CMP and slurry		
-	107822	@ad>20020109 or @rlad>20020109	USPAT;	2003/04/24
			US-PGPUB	14:28
-	113	(conductive and dielectric and "silicon oxynitride" and	USPAT;	2003/04/24
		"titanium nitride" and (via or hole or opening or trench) and	US-PGPUB	14:54
		tungsten and CMP and slurry) not (@ad>20020109 or		
		@rlad>20020109)	****	, ,
-	449	platen with "polishing pad" with slurry	USPAT;	2003/04/24
	_ [	((CiON on "ailion or mitmida") and the contract of the	US-PGPUB	15:47
-	0	((SiON or "silicon oxynitride") with remov\$3 with (slurry or	USPAT;	2003/04/24
_		solution)) and (platen with "polishing pad" with slurry)	US-PGPUB	15:47
-	2	(conductive and dielectric and "silicon oxynitride" and "titanium nitride" and (via or hole or opening or trench) and	USPAT;	2003/04/24
		tungsten and CMP and slurry) and (platen with "polishing	US-PGPUB	15:48
		pad" with slurry )		
		pau with starry)	<u> </u>	